

JUN 07 2004

AMENDMENTS TO THE CLAIMS

Claims 1-2 (Canceled)

Claim 3 (Previously Presented) A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

increasing a rotational speed of the dresser if the surface of the polishing cloth is higher at an inner circumferential region of the polishing cloth than at an outer circumferential region of the polishing cloth.

Claim 4 (Previously Presented) A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

lowering a rotational speed of the dresser if the surface of the polishing cloth is higher at an outer circumferential region of the polishing cloth than at an inner circumferential region of the polishing cloth.

Claim 5 (Currently Amended) A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth mounted on a turntable, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

increasing a ratio of a rotational speed of the dresser turntable to a rotational speed of the turntable dresser if the surface of the polishing cloth is higher at an inner circumferential region of the polishing cloth than at an outer circumferential region of the polishing cloth.

Claim 6 (Currently Amended) A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth mounted on a turntable, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

lowering a ratio of a rotational speed of the dresser ~~turntable~~ to a rotational speed of the turntable dresser if the surface of the polishing cloth is higher at an outer circumferential region of the polishing cloth than at an inner circumferential region of the polishing cloth.